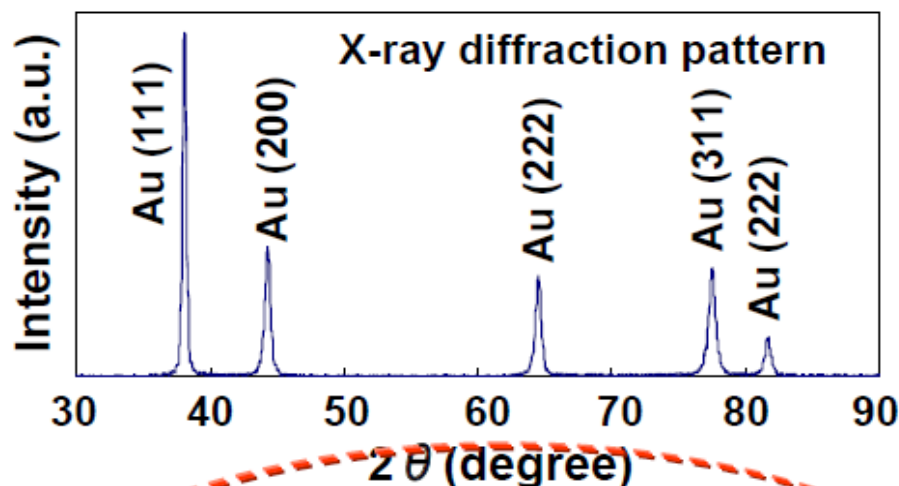


# Introduction of Low Temperature Au-to-Au Submicron Bonding Material

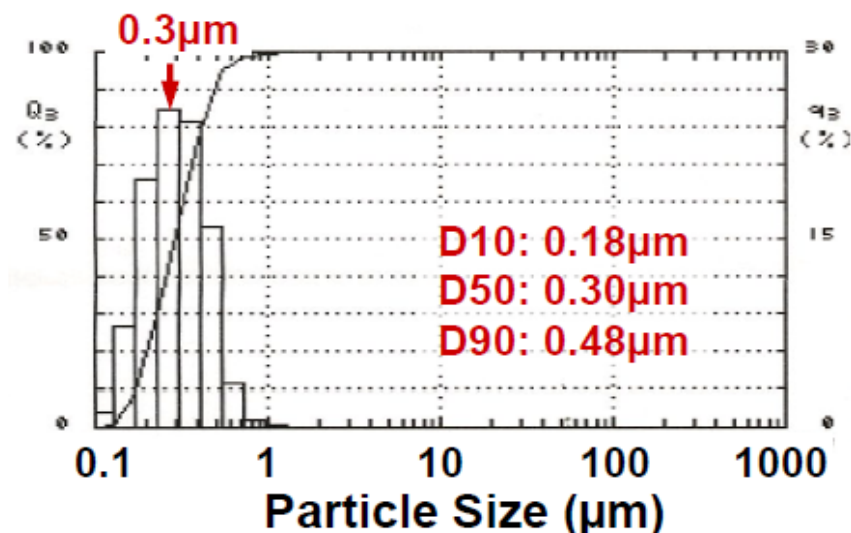
May 3, 2016

# Characteristics of Sub-micron Au Particles

- High Purity Au Particles

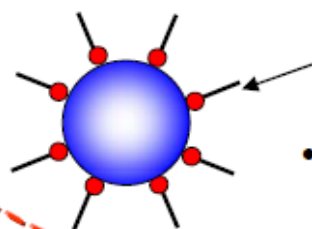


- Particle Size Control



- Surface Preparation of Au Particles

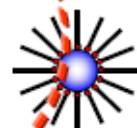
## Sub-micron particles



Surface active agent  
(Physically bonded)

- Can be removed at low temp  $>100^{\circ}\text{C}$

## Nano-particles



Organic shell  
(Chemically bonded)

- Need to heat up to higher temp. to remove

# Low-temperature Bonding material

## AuRoFUSE™



- AuRoFUSE™ TR-191R
- 200Pa·s, 95mass%Au
- Distribution 0.2-0.5  $\mu$ m

- Screen printing
- Halogen free solvent
- No cleaning process
- RT. storage for 3 month

# Typical Properties of AuRoFUSE™

PASTE PROPERTIES	TR-191R	80Au20Sn (mass%)
Viscosity	200 Pa·s (Shear rate 20/s)	—
Au content	95 mass%	—
Au diameter	0.2-0.5 $\mu$ m	—
Shelf life	3 Month (Jars, <25°C)	—
	3 Month (Syringes, <25°C)	—
Ionic impurities	Cl <sup>-</sup> < 10ppm, K <sup>+</sup> < 10ppm, Br <sup>+</sup> < 10ppm Na <sup>+</sup> , F <sup>-</sup> : under investigation	—
BONDED PROPERTIES	230°C heating in air (No pressure)	300°C soldering with Flux (No pressure)
Electrical resistivity	5.4 $\mu$ $\Omega$ cm (25°C)	27.6 $\mu$ $\Omega$ cm (25°C)
Thermal conductivity	150 W / mK	57.3 W / mK
Heat-resistant	1064 °C (melting point)	278 °C (melting point)
Young's modulus	9.5 GPa (25°C)	60 GPa (25°C)
Shear strength	40 MPa ※1	100 MPa
Au content	99.95 mass%	80 mass%
UBM	Au finish	Au / Ni

※1) "Ar plasma cleaning" against bonding surface of Au finish is recommended to eliminate the surface contamination such as some oxidations of under barrier metals Ni, Cu, Ti etc., resulting in the increment of shear strength.

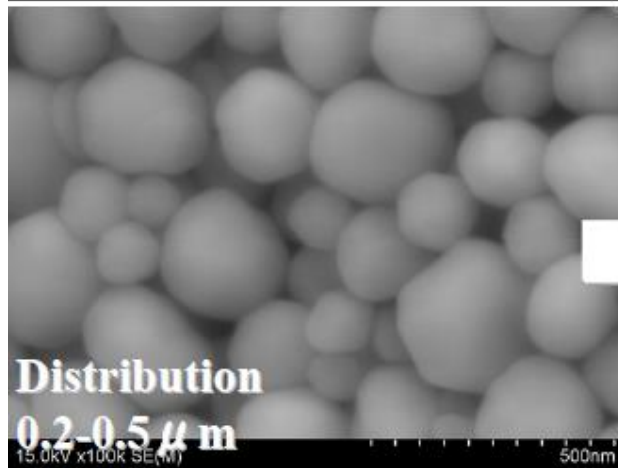


# Motivation of Sub-micron Au Particles to Interconnections of Functional Device

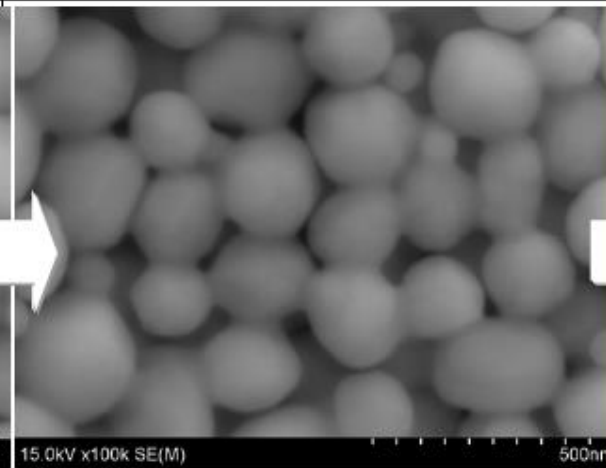
Features of Au particles	Features of interconnections
Low temperature bonding due to the sintering behavior of Au particles.	<ul style="list-style-type: none"><li>• Reduced heat damage of components</li><li>• Lower residual stress to devices</li><li>• Small pitch and multiple bonding with no pressure</li></ul>
Sintered compact consists of a number of <i>Au/Au metal joints</i> .	<ul style="list-style-type: none"><li>• Low electrical resistance (<math>&lt; 5 \times 10^{-6} \Omega \text{ cm}</math>)</li><li>• High thermal conductance (<math>&gt; 150 \text{ W/m} \cdot \text{K}</math>)</li><li>• Heat resistance of joint (mp: <math>1063^\circ \text{C}</math>)</li></ul> <p><b><math>\Rightarrow</math> Die-bonding application</b></p>
Compressive deformation of sintered compact leads to a <i>densely structure</i>	<ul style="list-style-type: none"><li>• Hermetic sealing (leak rate <math>&lt; 1 \times 10^{-13} \text{ Pa} \cdot \text{m}^3/\text{s}</math>)</li><li>• Tolerance of surface roughness (<math>&lt; \pm 3 \mu\text{m}</math>)</li></ul> <p><b><math>\Rightarrow</math> Hermetic sealing application</b></p>

# Sintering Behavior of Sub-micron Au Particles

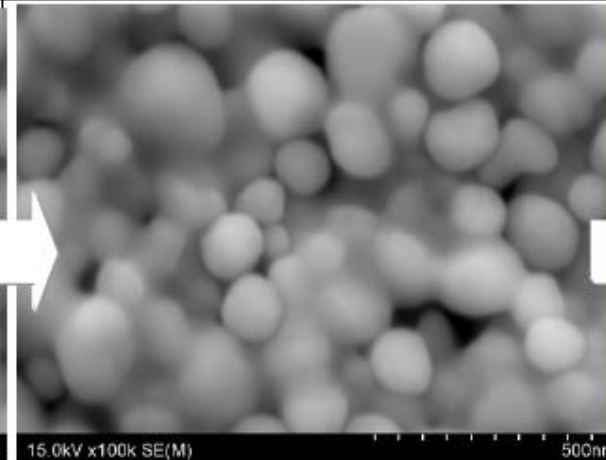
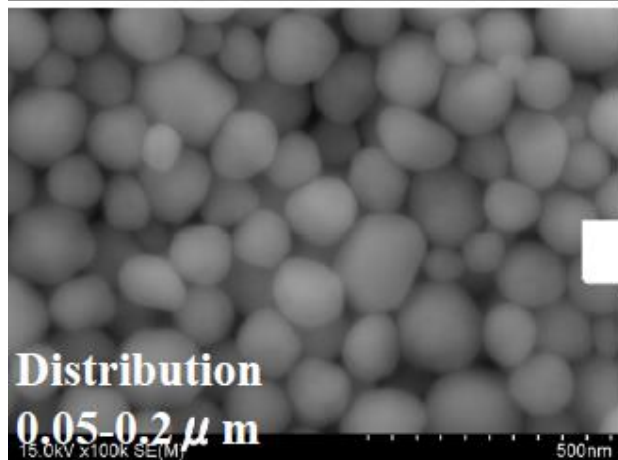
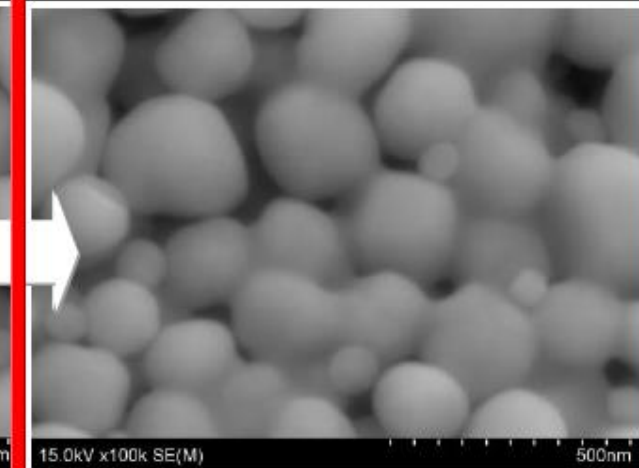
100°C • 5min



150°C • 5min



200°C • 5min



Necking of Au particles is observed above 150°C in air with no pressure.

# Motivation of Sub-micron Au Particles to Interconnections of Functional Device

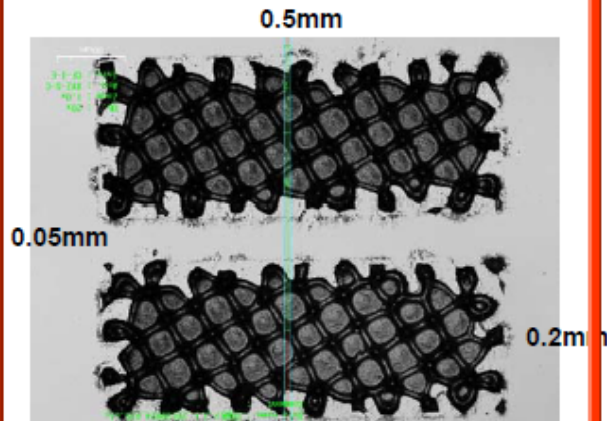
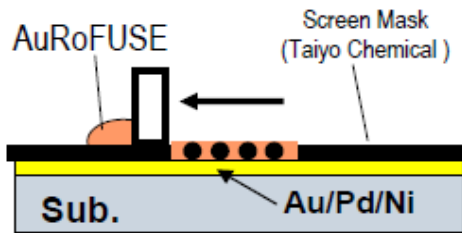
Features of Au particles	Features of interconnections
<i>Low temperature bonding due to the sintering behavior of Au particles.</i>	<ul style="list-style-type: none"><li>•Reduced heat damage of components</li><li>•Lower residual stress to devices</li><li>•Small pitch and multiple bonding with no pressure</li></ul>
<i>Sintered compact consists of a number of Au/Au metal joints.</i>	<ul style="list-style-type: none"><li>•Low electrical resistance (<math>&lt; 5 \times 10^{-6} \Omega \text{ cm}</math>)</li><li>•High thermal conductance (<math>&gt; 150 \text{ W/m} \cdot \text{K}</math>)</li><li>•Heat resistance of joint (mp:1063°C)</li></ul> <p><b>⇒ Die-bonding application</b></p>
<i>Compressive deformation of sintered compact leads to a densely structure</i>	<ul style="list-style-type: none"><li>•Hermetic sealing (leak rate <math>&lt; 1 \times 10^{-13} \text{ Pa} \cdot \text{m}^3/\text{s}</math>)</li><li>•Tolerance of surface roughness (<math>&lt; \pm 3 \mu\text{m}</math>)</li></ul> <p><b>⇒ Hermetic sealing application</b></p>

# **Development of Die-bonding for LED**



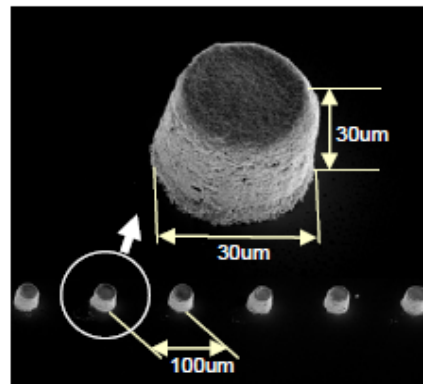
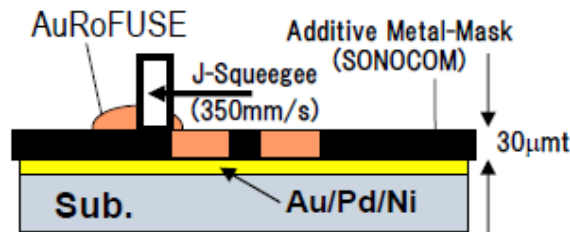
# High-precision Screen Printing (LS-150, NEWLONG)

## Film Printing



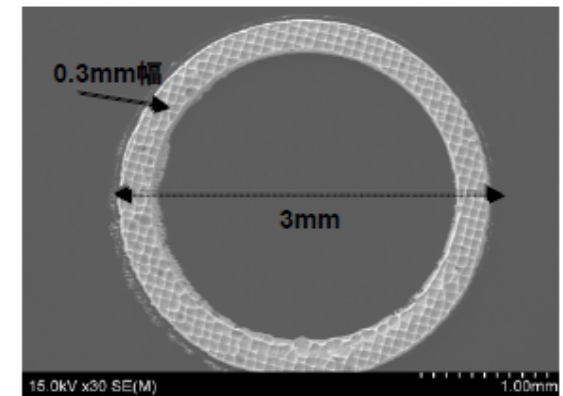
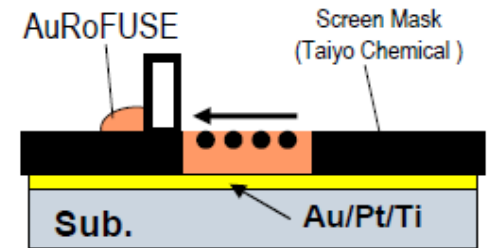
Die-bond joint for LED, P/D

## Bump Printing



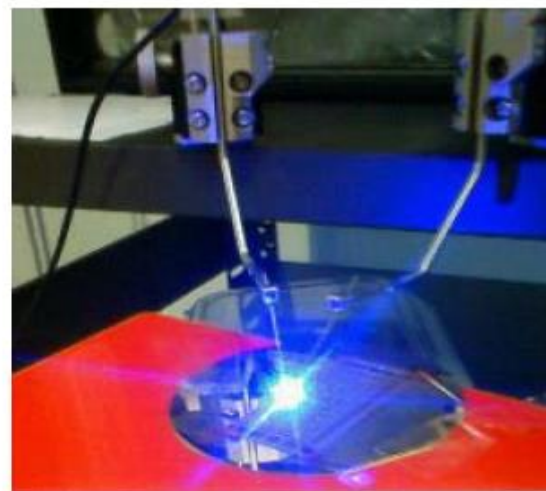
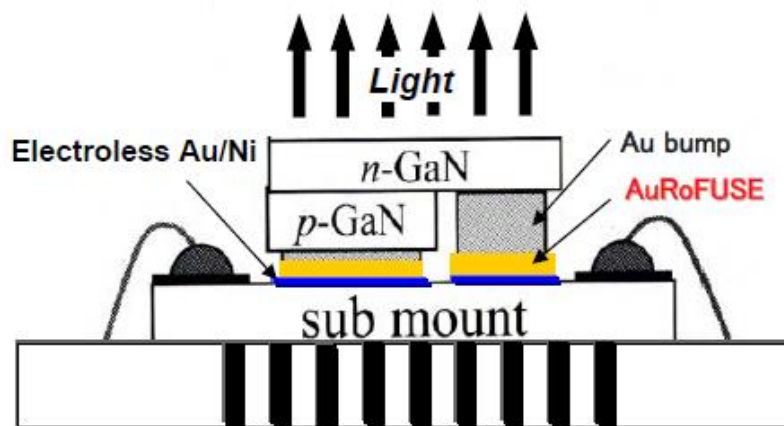
FC joint for LED

## Ring Printing

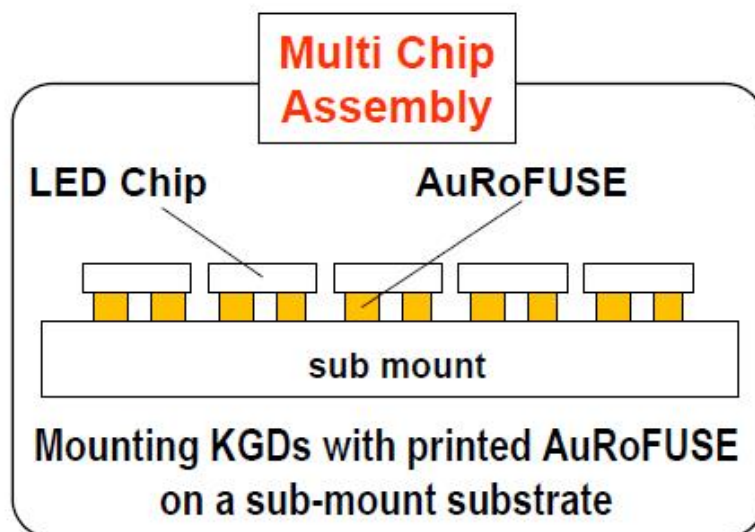


Hermetic sealing for MEMS

# Assemble of Flip-Chip LED



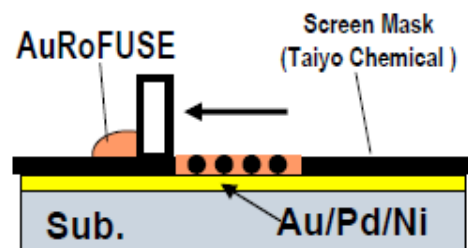
Lightening of 200mW LED chip



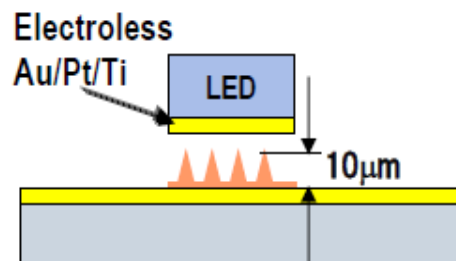
Reliability Tests	
Die Shear Strength (MPa)	4 items
Thermal Transient (K/W)	2 items
Electric Resistance ( $\Omega$ )	3 items

# Film Printing of TR-191R for Die-bonding

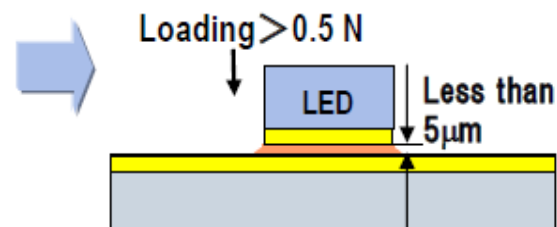
## 1. Printing (off-contact)



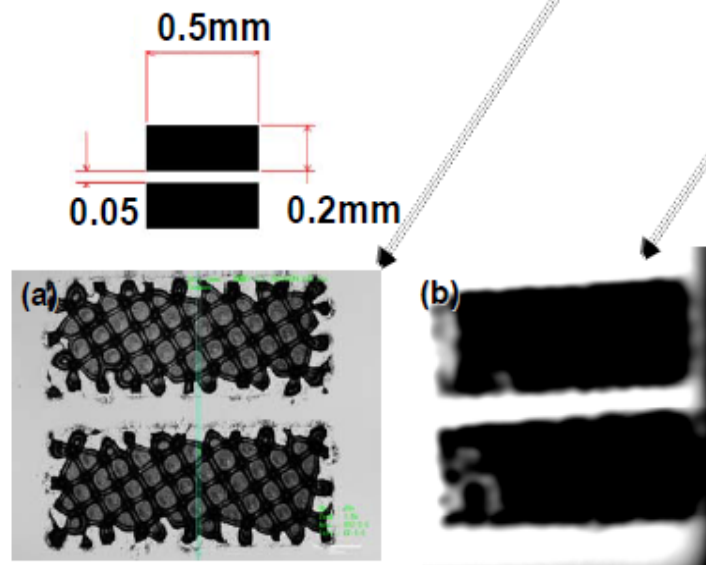
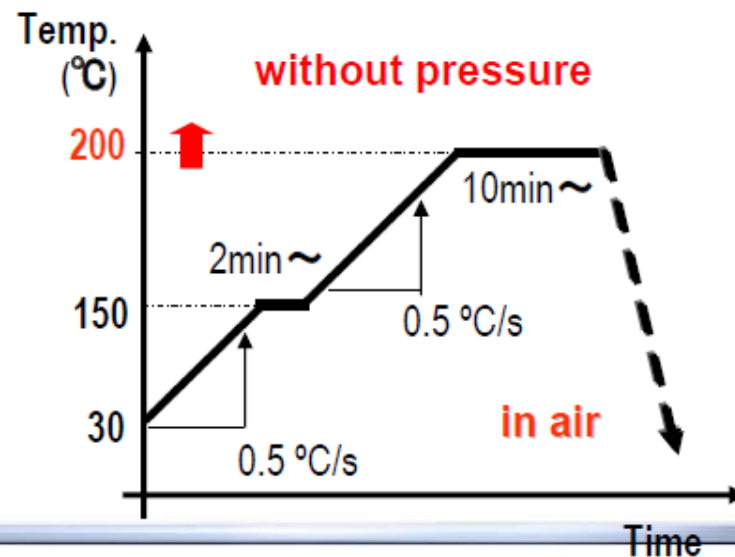
## 2. Alignment



## 3. Mounting (RT)

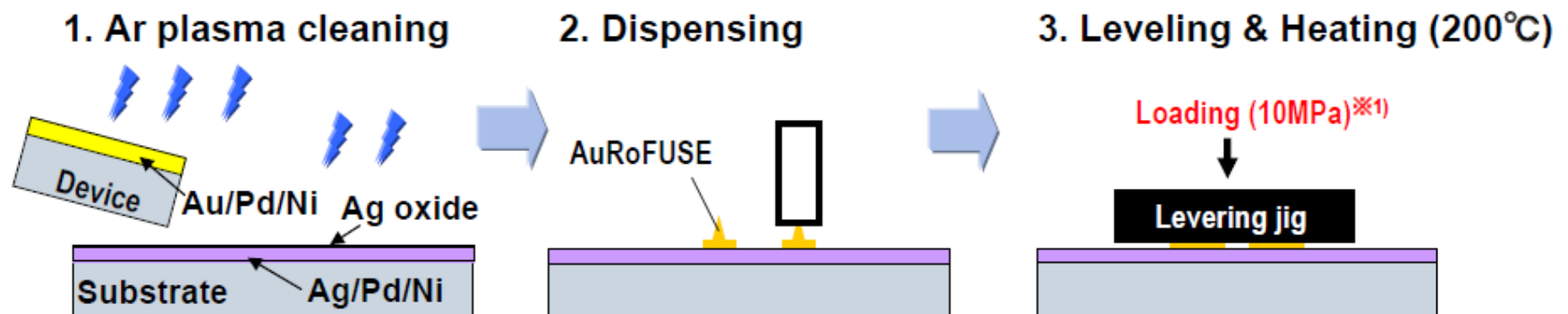


## 4. Heating

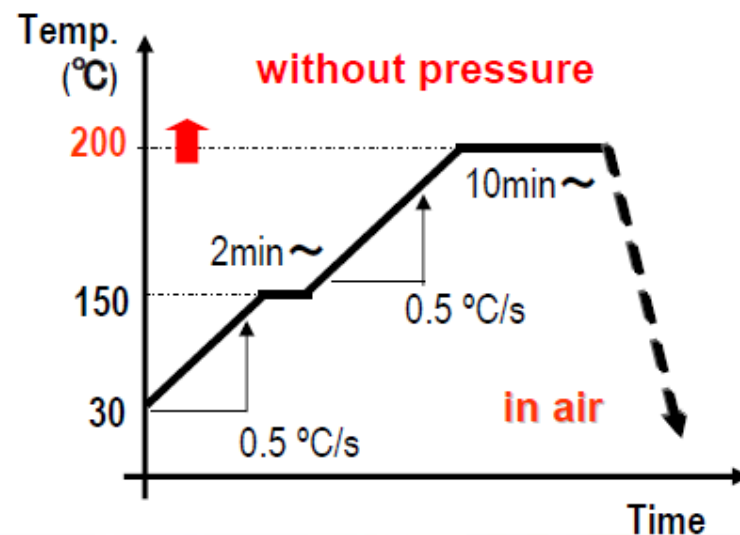
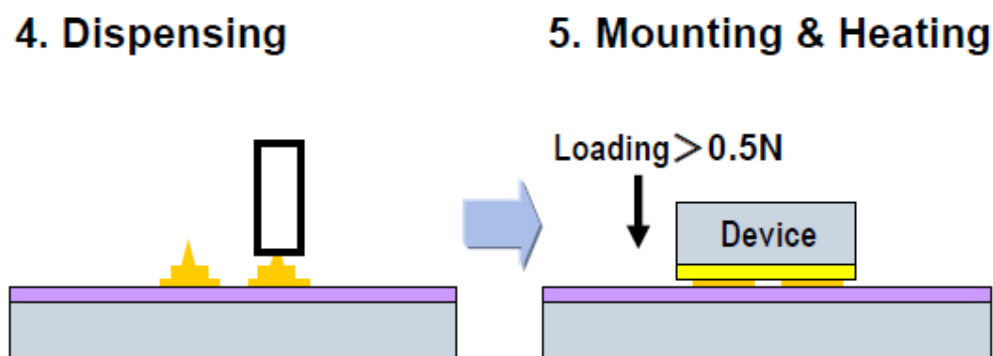


Before (a) and after (b) mounting of LED electrode size and pitch

# Dispensing of TR-191R for FC joints having Ag finished electrodes



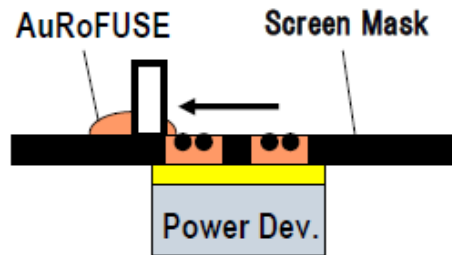
※1) depend on Ag surface cleanness



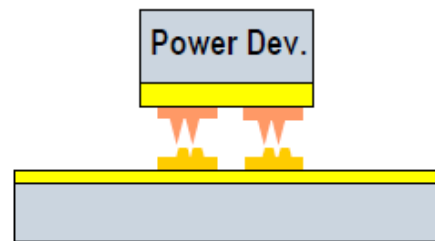


# Film Printing of TR-191R for die-bonding

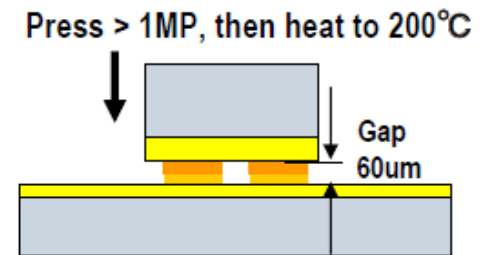
## 3. Printing (off-contact)



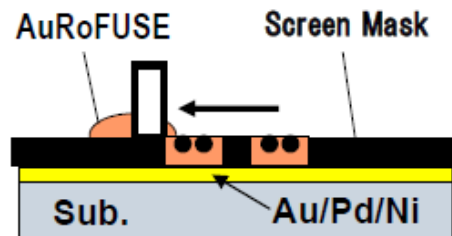
## 4. Alignment by flip-chip bonder



## 5. Mounting (RT) & pre-sintering (200°C)



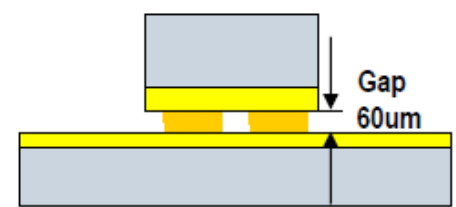
## 1. Printing (off-contact)



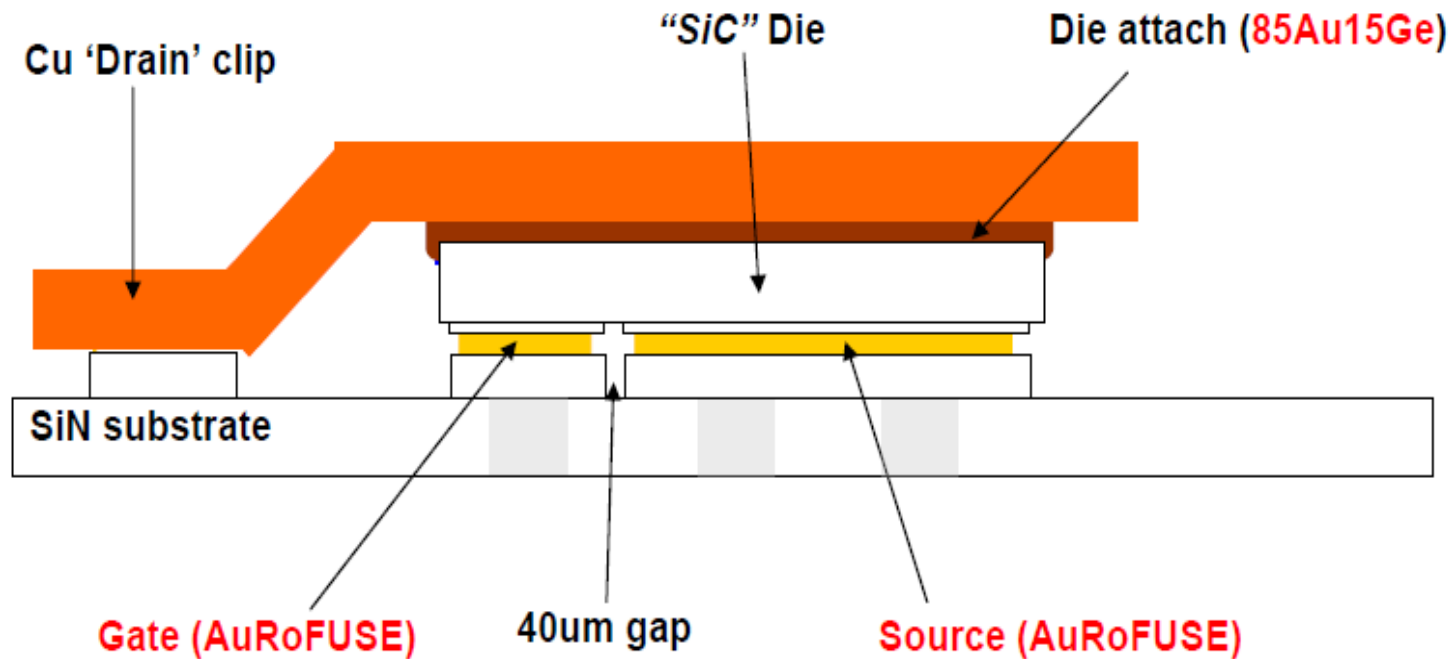
## 2. Pre-sintering (200°C) & leveraging



## 6. Sintering (250°C 2h) by oven furnace



# Structure of Double-Side Bonded Power Module



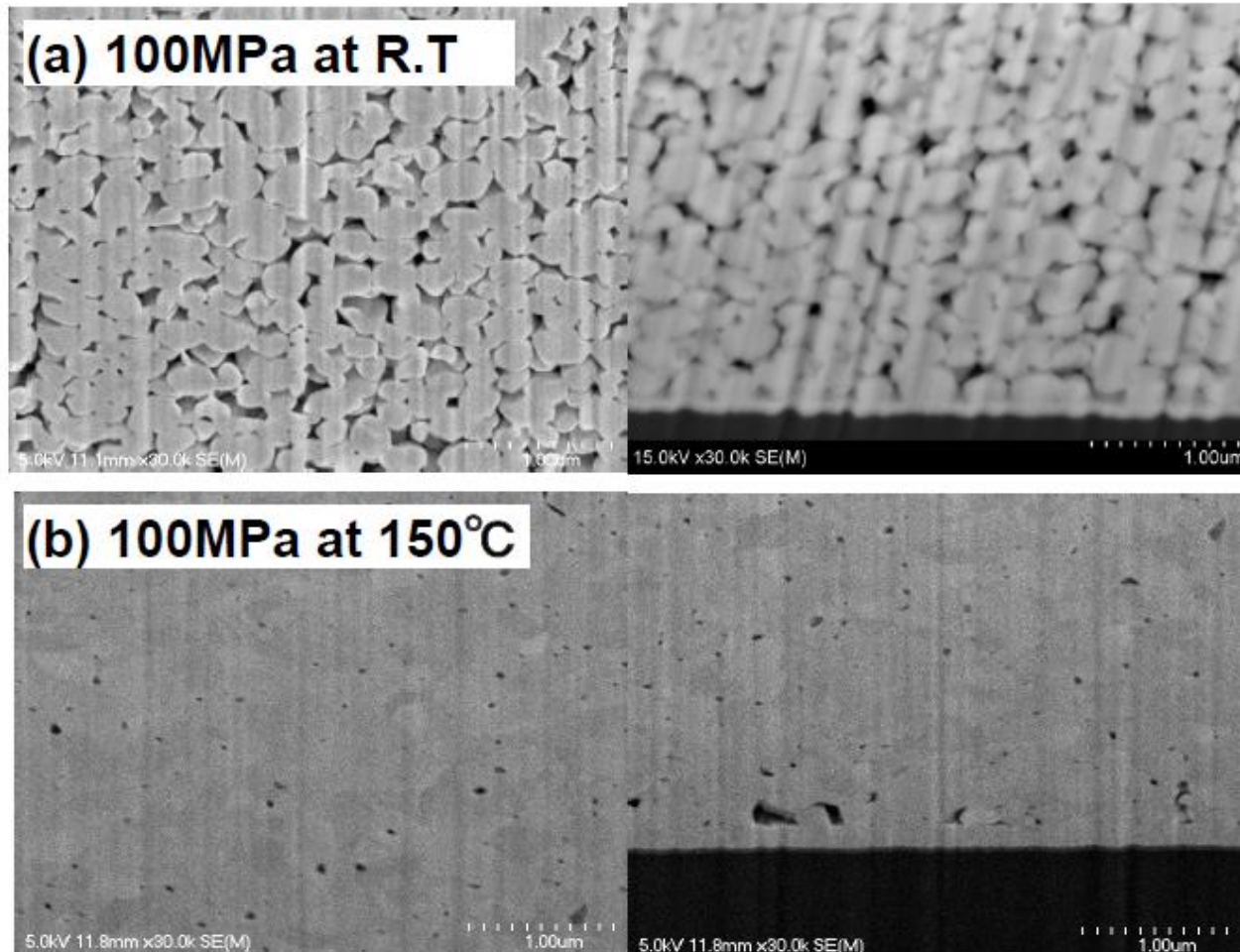
# Motivation of Sub-micron Au Particles to Interconnections of Functional Device

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Compressive deformation of sintered compact leads to a <i>densely structure</i>	<ul style="list-style-type: none"> <li>• Hermetic sealing (leak rate <math>&lt; 1 \times 10^{-13} \text{ Pa} \cdot \text{m}^3/\text{s}</math>)</li> <li>• Tolerance of surface roughness (<math>&lt; \pm 3 \mu\text{m}</math>)</li> </ul> <p><b><math>\Rightarrow</math> Hermetic sealing application</b></p>

# **Development of Hermetic Sealing MEMS**



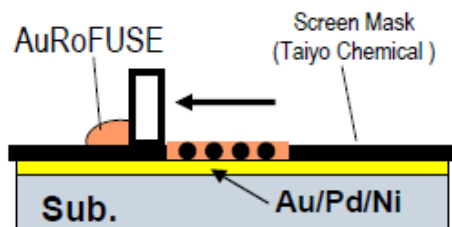
# What's Hermetic Sealing by Au Sintered Compacts?



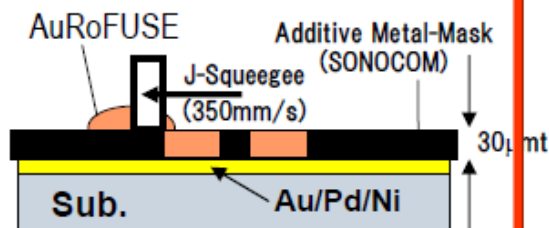
To get a densely structure changing from open pore state to closed pore state by thermo-compression bonding.

# High-precision screen printing (LS-150, NEWLONG)

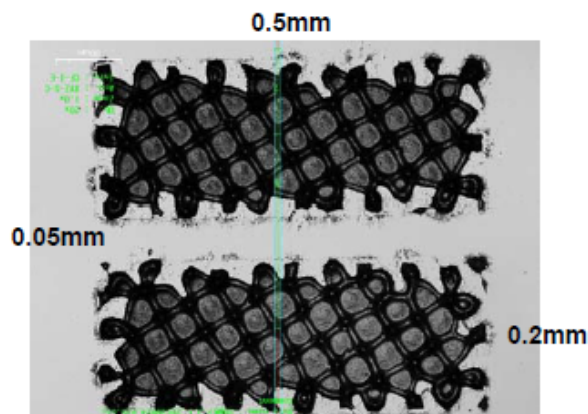
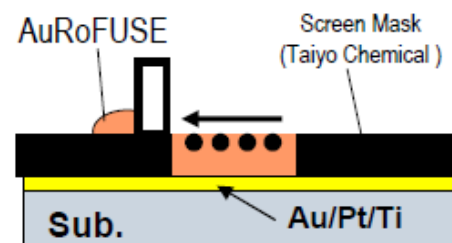
## Film Printing



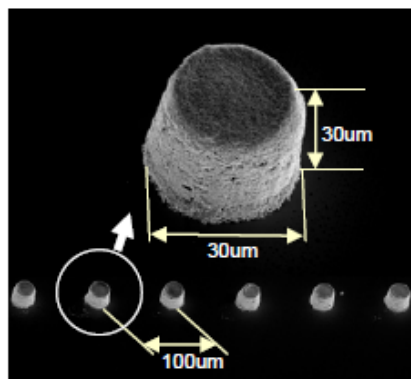
## Bump Printing



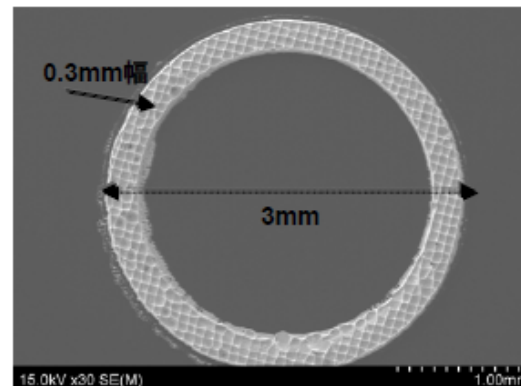
## Ring Printing



Die-bond joint for LED, P/D



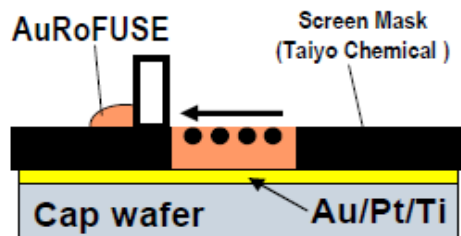
FC joint for LED



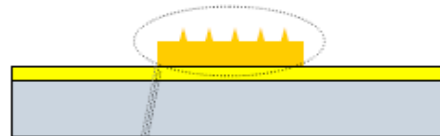
Hermetic sealing for MEMS

# Ring Printing of TR-191R for Hermetic Sealing

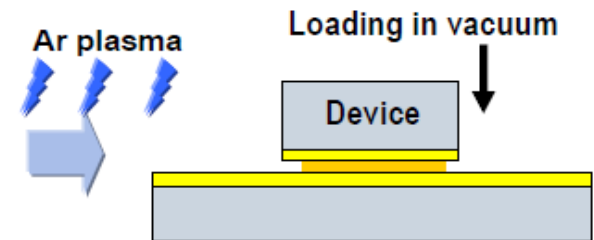
## 1. Printing (off-contact)



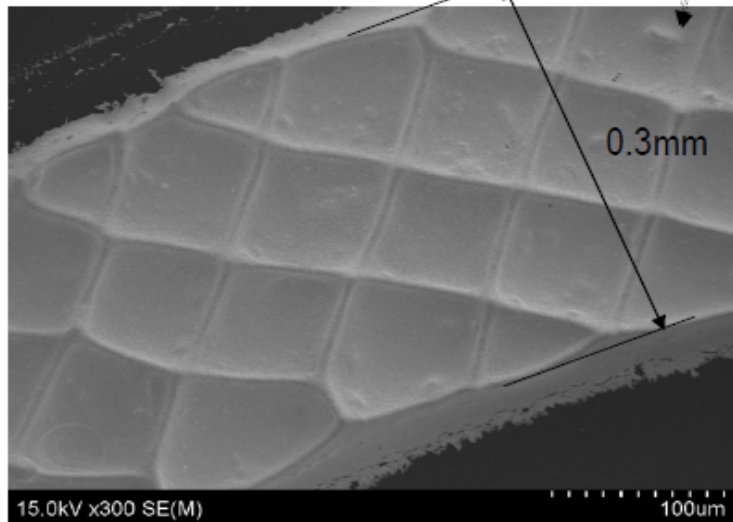
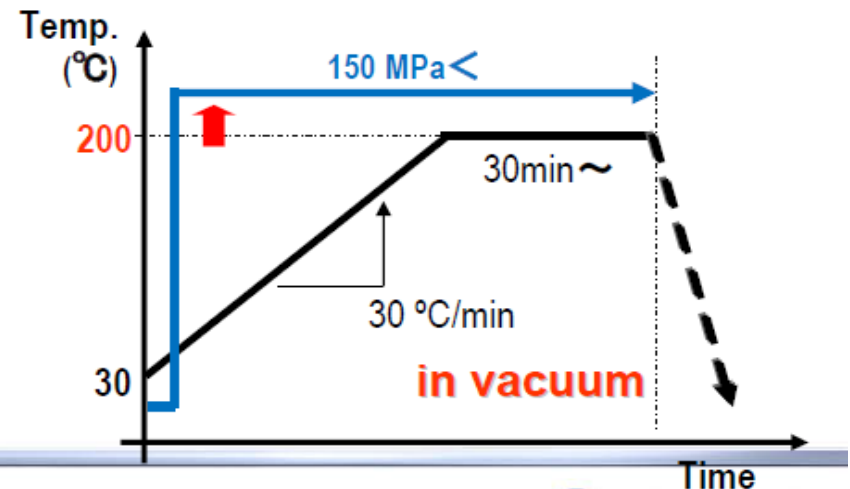
## 2. Pre-sintering & outgas reduction (200°C, Ar-4%H<sub>2</sub>, cycle purge)



## 3. Alignment (RT) & bonding (200°C)

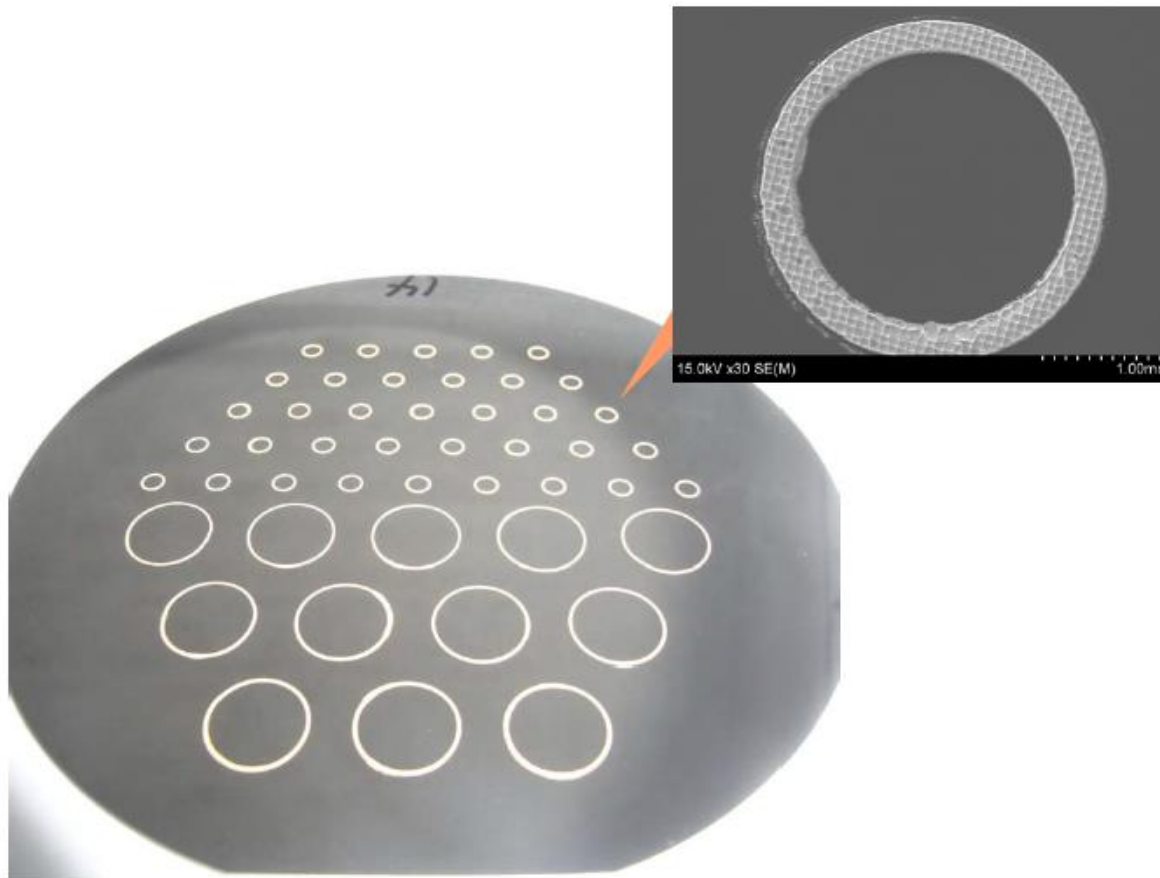


## 4. Bonding profile for hermetic sealing



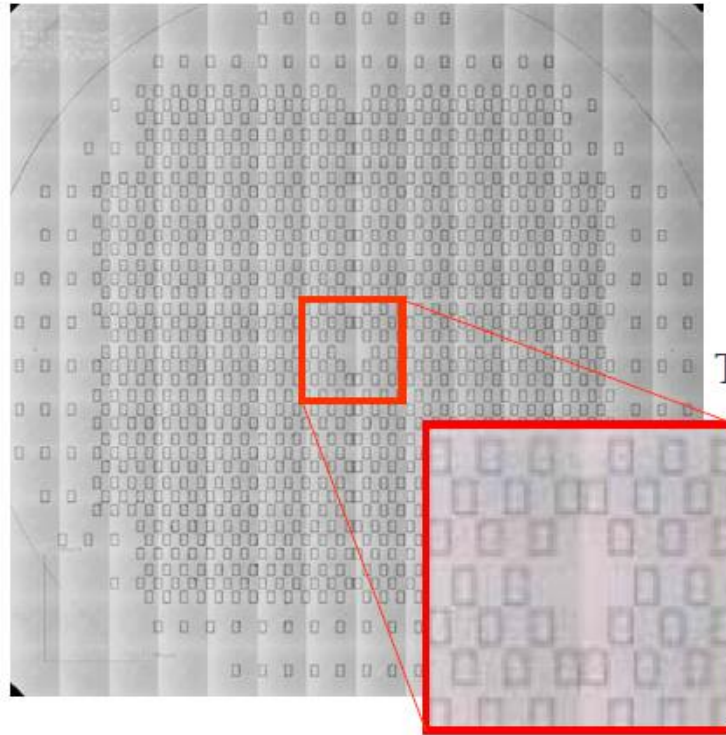
Printed network structure

# Ring Patterns of Au sintered Compacts by Screen Printing on 4 in. wafer



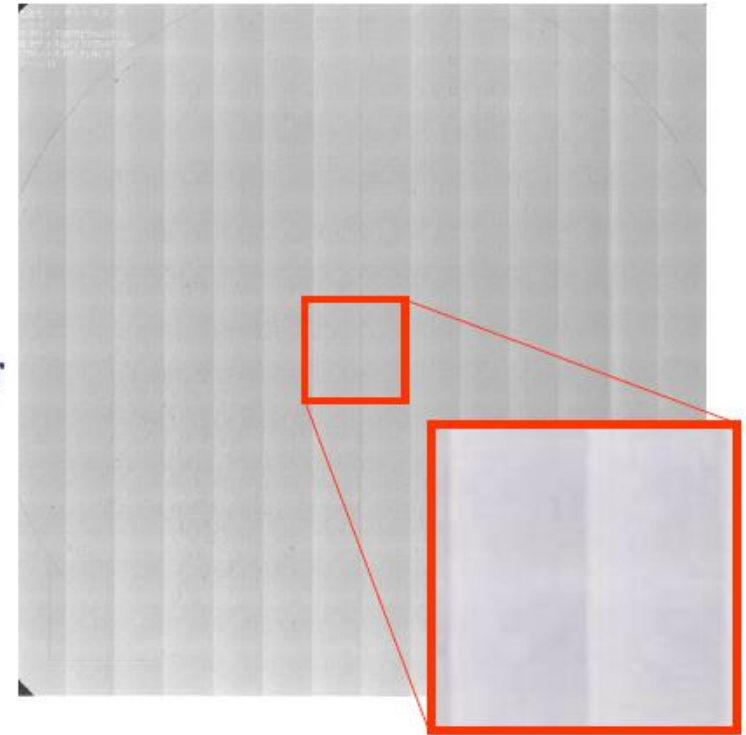


# Wafer level Au pattern transfer for hermetic seal rings



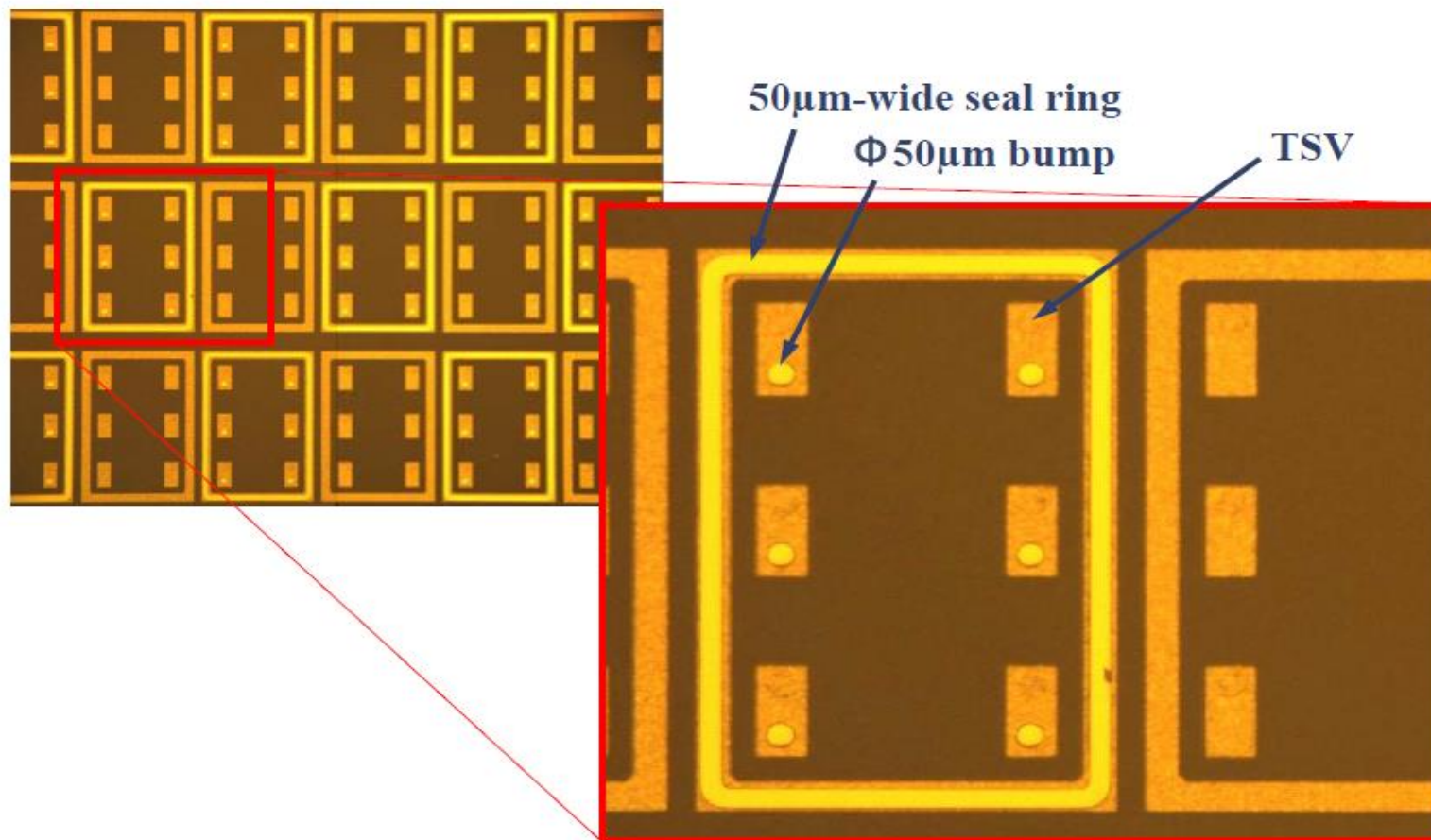
**Initial Transfer Wafer**  
(before transfer)

➔  
**Transfer**

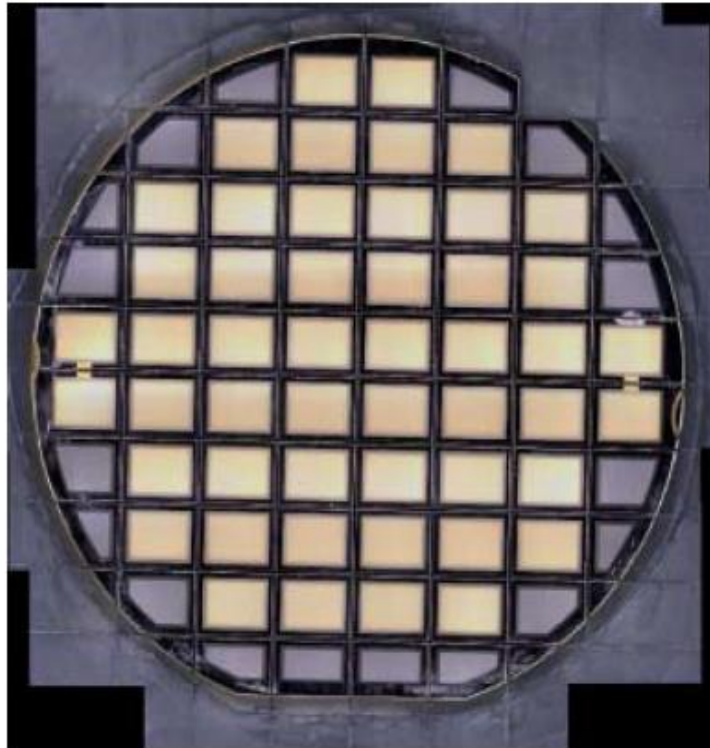


**After Transfer**

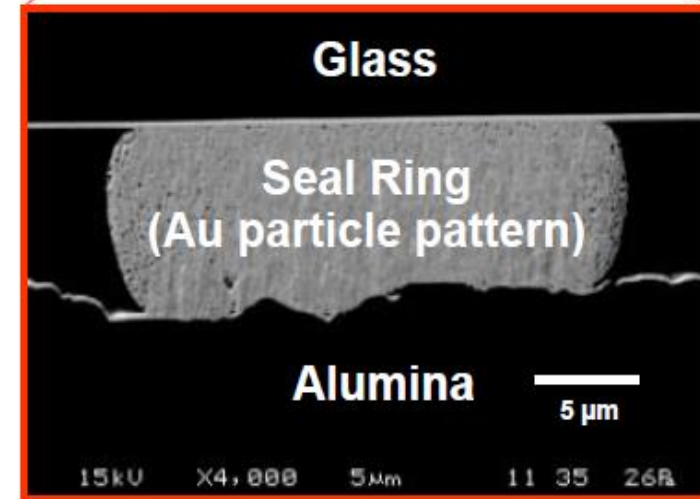
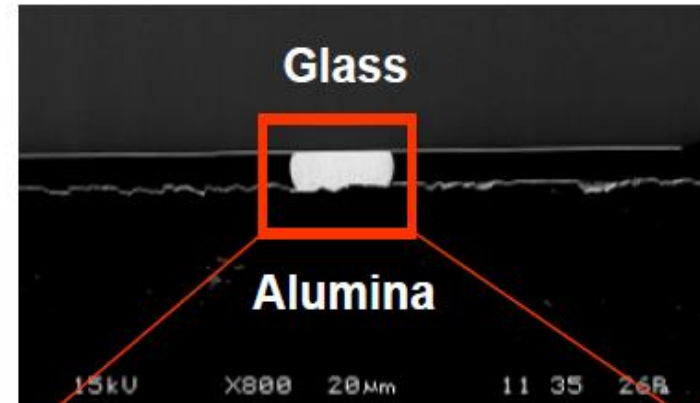
# Transferred Pattern Result: Sealing Lines and Bumps onto Ceramic Substrate



# Surface-Compliant Behavior of Sub-Micron Au Particle Patterns



Φ2" bonded pair (glass + alumina)  
at 200°C, 200MPa, 30min.  
Blade-dicing was successfully done.  
**He leak rate < 1x10<sup>-13</sup> Pa·m<sup>3</sup>/s**



Cross-section SEM images of  
a 20μm-wide seal ring



# Conclusions

1. **Low temperature sintering** of sub-micron Au particles is suited to low temperature bonding with no pressure leading to less damage of functional devices.
2. **Au/Au metal joint** of sub-micron Au particles showing a low electrical resistance, high thermal conductance is applied to LED and P/D assembly.
3. Wafer-level packaging was successfully performed due to **easy deformation of porous structure**, and He leak rate of  $< 1 \times 10^{-13}$  Pa·m<sup>3</sup>/s was obtained for the bonded pairs between glass and Al<sub>2</sub>O<sub>3</sub> wafers even if it has a surface irregularity.



# Thank You For Your Attention!

